

# **IEEE SW Test Workshop**

Semiconductor Wafer Test Workshop

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Oxford Lasers



## **Comparison of Drilling Rates and Tolerances of Laser-Drilled holes in Silicon Nitride and Polyimide Vertical Probe Cards**



**June 8-11, 2008**  
**San Diego, CA USA**

# Overview

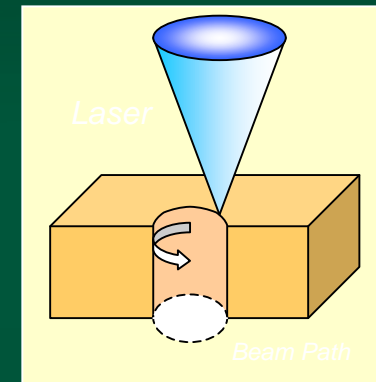
- Introduction to laser drilling
- Laser drilling examples
- Comparison of laser drilling of SiN and polyimide
- Comparison of laser drilling with mechanical drilling
- Summary



# Introduction to Laser Drilling

## for Vertical Probe Cards

- Laser beam diameter at focus - typically 0.2 mil ( $5\mu\text{m}$ )
  - this is the diameter of the “laser drill-bit”
- Typical required hole diameters are 1.6 mil ( $40\mu\text{m}$ ) to 4 mil ( $100\mu\text{m}$ )
- Latest Systems rotate the beam around the hole center
  - this gives excellent hole circularity
- Laser beam evaporates the material
  - so the laser does not care if the material is hard or soft etc



# Introduction to Laser Drilling

## for Vertical Probe Cards

- Laser drilling machine looks and behaves like a modern wafer fab tool
- Latest developments include full software control of the process and hole geometry
- Flexible tool
  - can drill ceramics, polymers, silicon and other materials
- Future proof
  - hole diameters down to 0.8mil (20 $\mu$ m)
  - round holes, rectangular holes & other shapes



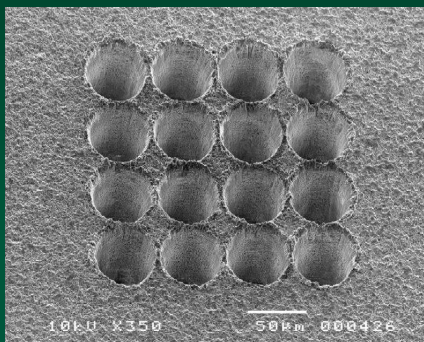
# Silicon Nitride and Polyimide

	SiN	Polyimide
Temperature	1900 °C sublimes	400 °C glassifies
Ablation threshold	~2.5 J/cm <sup>2</sup>	~0.05 J/cm <sup>2</sup>

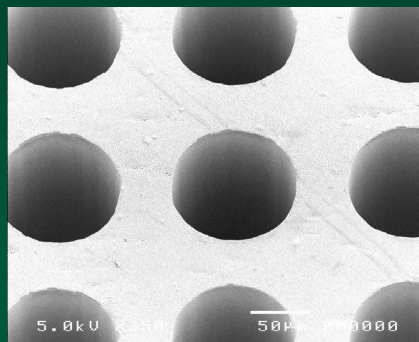
- means that it needs more laser power to ablate SiN
- expect process speed of SiN to be slower
- SiN sublimation means that it ablates very cleanly, no melt etc
- too much laser power on polyimide can cause charring



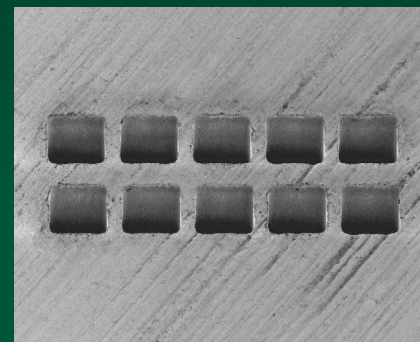
# Laser Drilling Examples



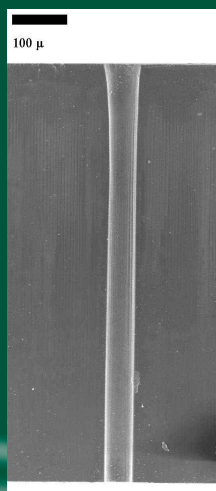
2 mil dia hole, alumina



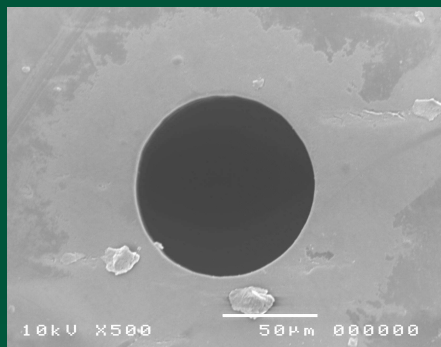
4 mil diameter hole, polyimide



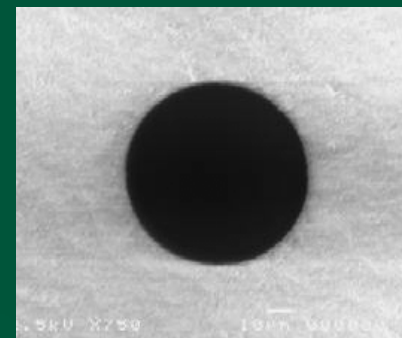
2.4 mil rectangular, SiN



2 mil dia hole, polyimide



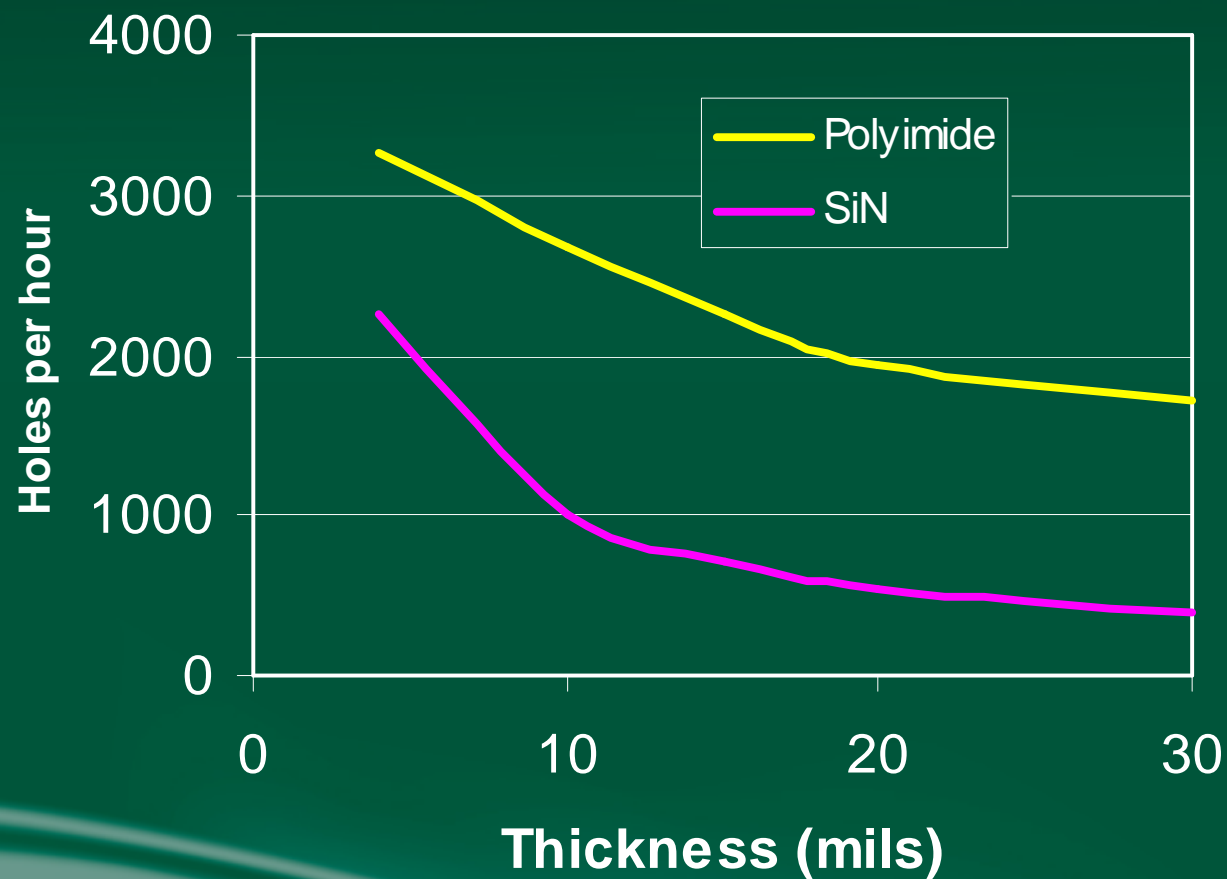
3.2 mil dia hole, polyimide



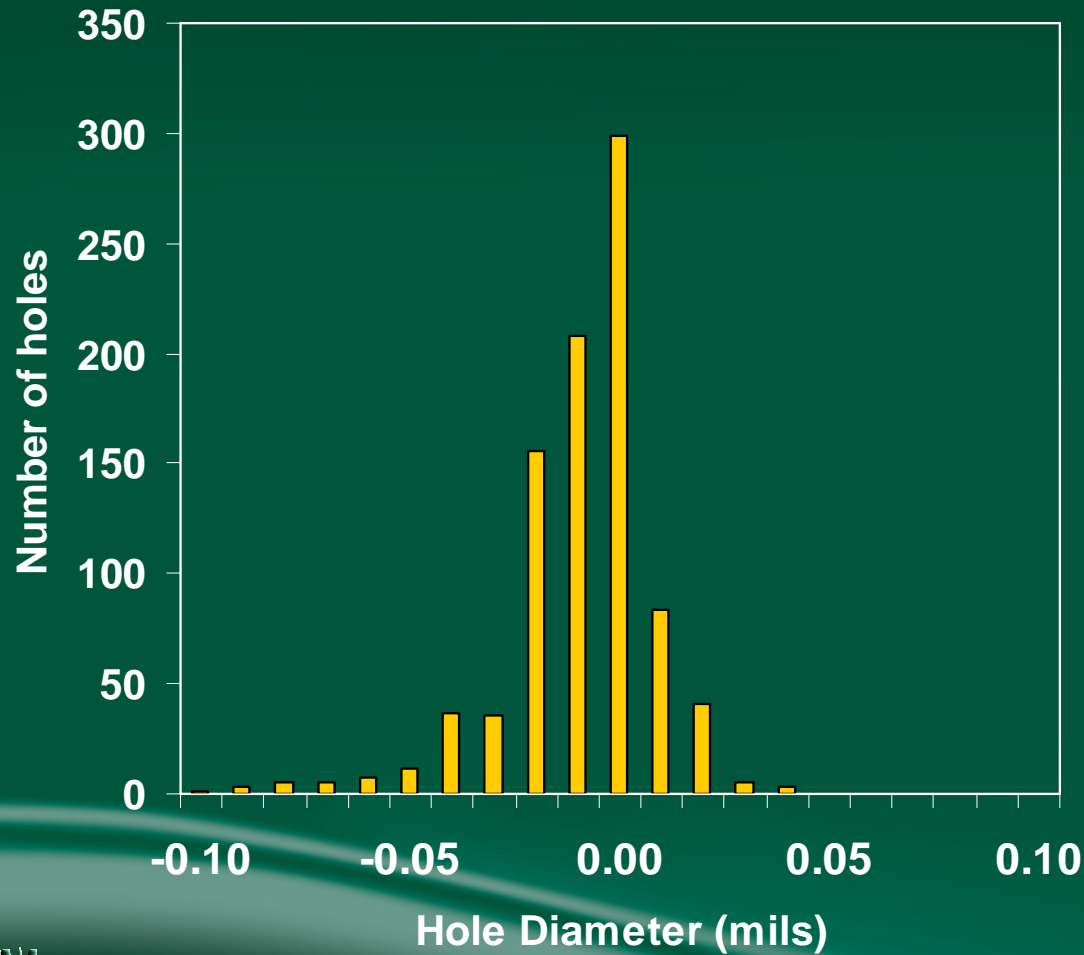
3.2 mil dia hole, SiN



# Laser Drilling - Process Rate



# Laser Drilling Diameter Accuracy



Diameter Variation  
0.07 mil (+/-2σ)

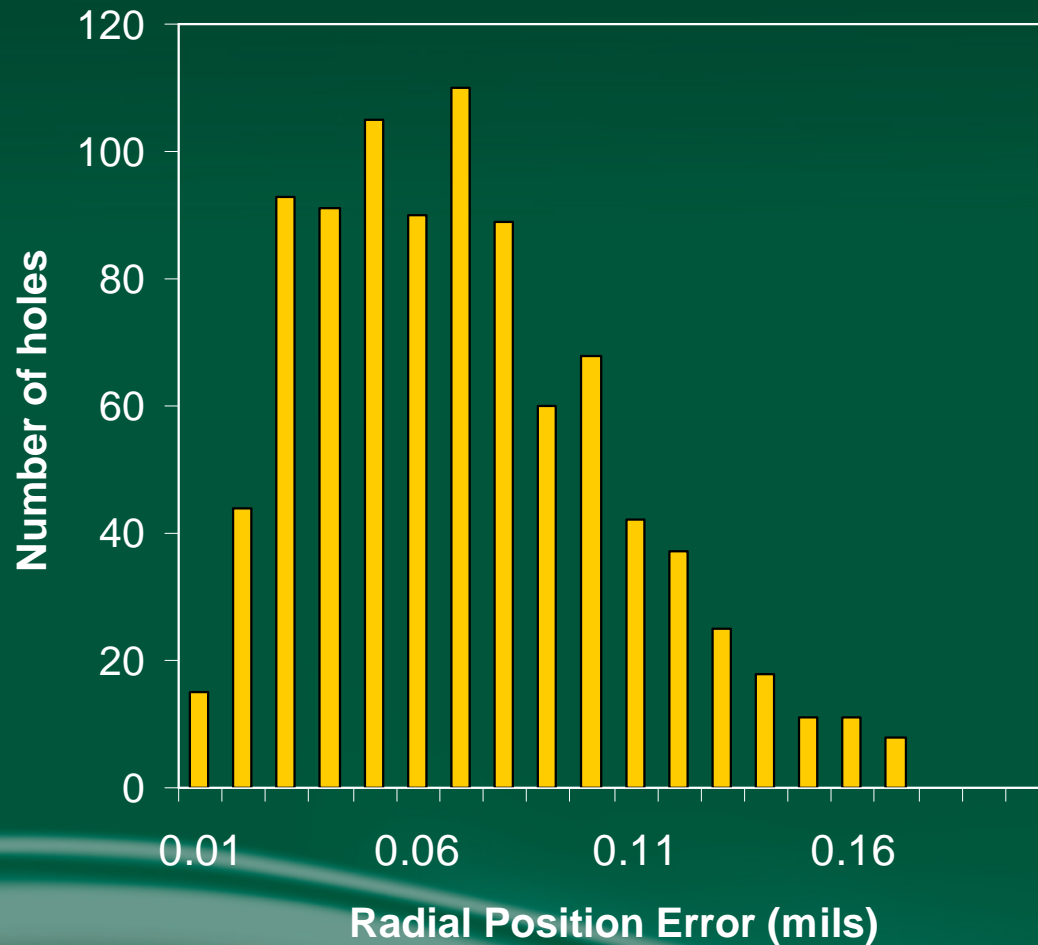
Circularity Variation  
0.05 mil (+/-2σ)

Measured with  
Mitutoyo SQV 404 PT

Resolution 0.004 mil



# Laser Drilling Position Accuracy



Radial position variation  
0.15 mil ( $\pm 2\sigma$ )

Measured with  
Mitutoyo SQV 404 PT

Resolution 0.004 mil

Accuracy 0.07 mil



# Probe Card Industry Challenge

From Intel presentation at SWTW 2007

## Technical challenge

- to meet next generation of probe cards

## Cost challenge

- to reduce probe card costs in line with other manufacturing costs



# Probe Card Industry Challenge

## Why we needed to find new alternative technologies

Next generation requirements extend past current capabilities.

Pitch  $\rightarrow$  175 $\mu$ m  $\longrightarrow$  X

Cu Bump  $\Phi$   $\rightarrow$  105 $\mu$ m  $\longrightarrow$  X

- Tighter scrub control capability
- Tighter alignment and scrub variance control

Parallel Sort  $\rightarrow$  2x  $\longrightarrow$  X

- Large array size
- High probe count (beyond 5000)



Bottom Line: Intel's current probe card suppliers cannot meet next generation technical requirements.

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# Probe Card Industry Challenge

## Why we needed to find new alternative technologies

- Current technologies bound to high cost
  - Manufacturing process is Labor intensive
  - Manufacturing Process highly complex
  - Cost scales with probe count
    - Limits the ability to extend to parallel sort



Bottom line: Probe card cost is the key limiter to Intel's wafer test process cost reduction capability.

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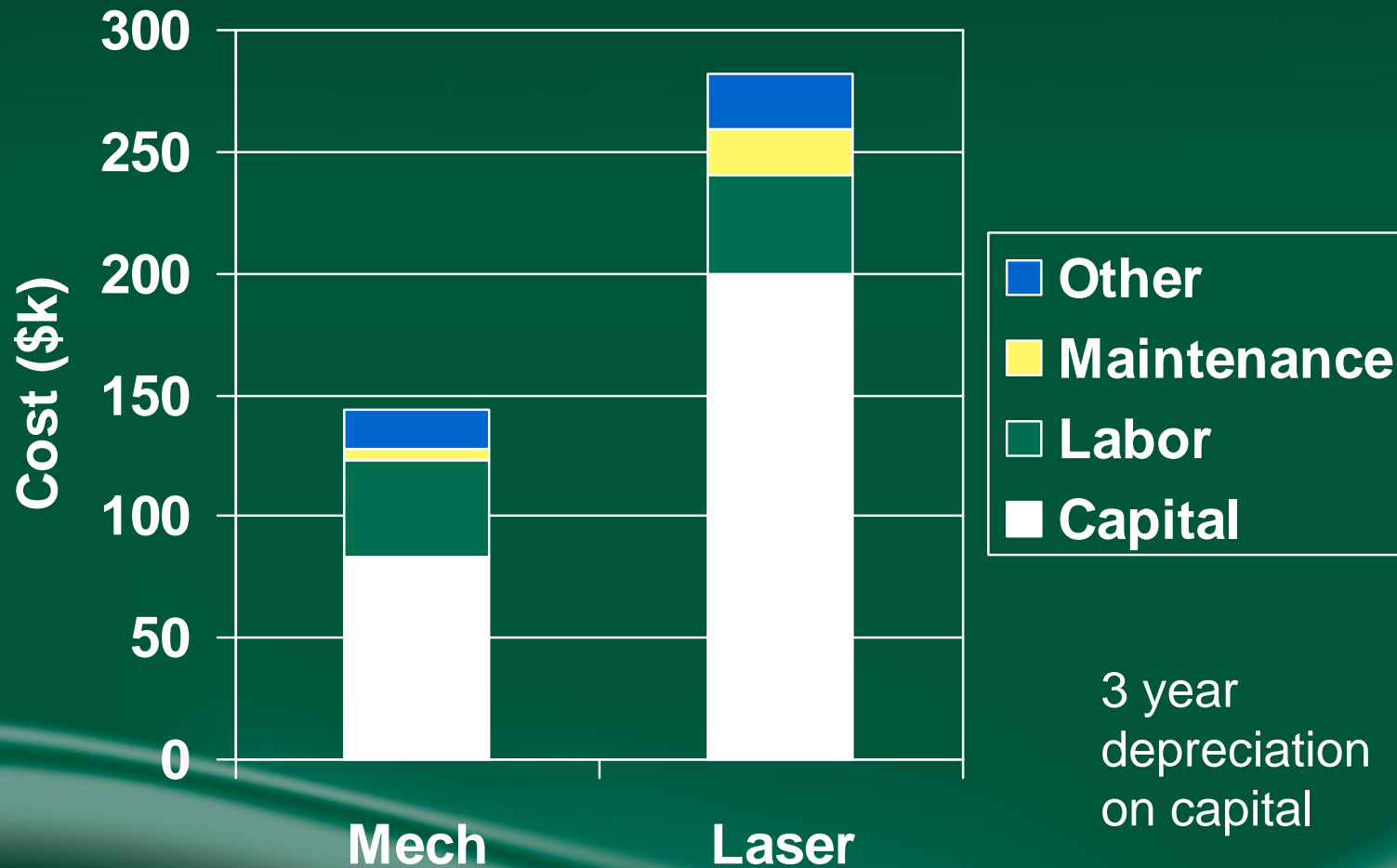


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# Laser & Mechanical Investment Costs per Year



# Mechanical versus Laser Drilling

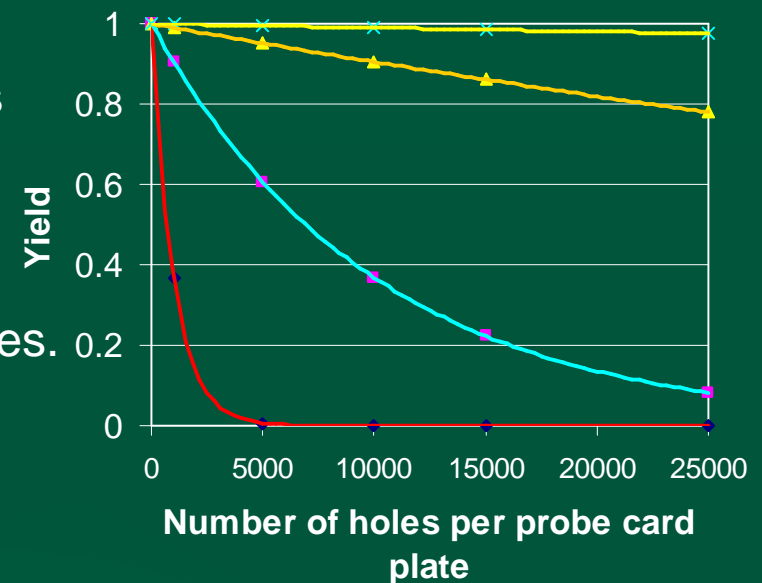
	Laser	Mechanical
Variation on Diameter	+/- 0.1 mil	+/- 0.1 mil
Process Complexity	Moderate	Moderate
Inherent Limitations	None	Drill Bit wear/breakage Drill Bit wander
Yield	>95%	70% - 98%
Drill time per hole	1 – 3 secs	4 – 15 secs
Time for 5000 holes	1.5 – 4.5 hours	6 – 21 hours



# Laser & Mechanical Drilling

## Effect of Hole Number on Yield

- Demonstrates that drilling process must be robust
- Mechanical drilling
  - yield is a strong function of number of holes
  - yield lies between the blue and orange curves
- Laser drilling
  - yield is a weaker function of number of holes
  - yield lies between the orange and yellow curves.



Calculation based on single hole success rates of  
99.9999%, 99.999%, 99.99%, 99.9%



# Laser & Mechanical Drilling

## Costs per hole - Silicon Nitride

### Assumptions

5000 hrs/yr  
3 mil dia hole  
10000 hole plate

	Mech	Laser
Holes/hr	360	1200
Yield	70%	95%
Cost/hr	36	55
Cost/1000 holes	144	48



# Laser & Mechanical Drilling

## Costs per hole - Polyimide

### Assumptions

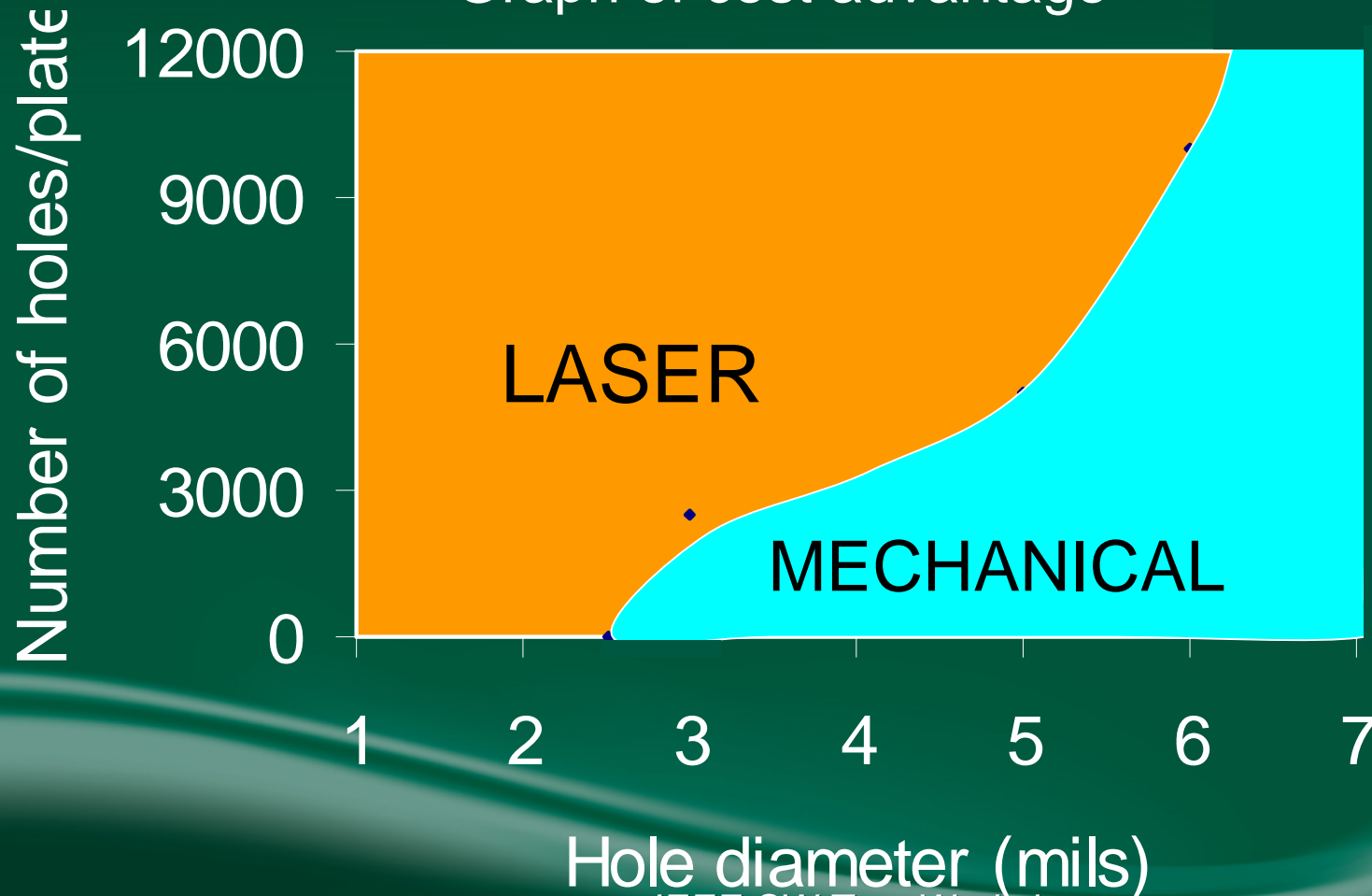
5000 hrs/yr  
4 mil dia hole  
10000 hole plate

	Mech	Laser
Holes/hr	600	2060
Yield	70%	95%
Cost/hr	36	55
Cost/1000 holes	87	28



# Laser versus Mechanical Drilling Cost Trade - Offs

Graph of cost advantage



# Conclusions

- Drilling Rates and Tolerances for Silicon Nitride and Polyimide have been reported
- Comparison between Mechanical and Laser drilling demonstrates the area where each is most cost competitive
- **Laser Drilling offers the capability to meet some of the challenges laid down by Probe Card customers**

